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CL	AA	5,269,879		12/14/93	Rhoades et al.		156	643				
EL	AB	Number										
Ec	AC	5,658,425		08/19/97	Halman et al.		438	620	70	33B		
EL	AD	5,685,914		11/11/97	Hills et al.		118	723	3083	BOO MAL ROOM		
ÊL	AE	5,780,338		07/14/98	Jeng et al.		438	253	37	J. 6		
EL	AF	5,783,496		07/21/98	Flanner et al.		438	743	R	L RG		
EL	AG	5,817,579		10/06/98	Ko et al.	438	740	2	OZ			
EC	АН	5,830,807		11/03/98	Matsunaga et al.	438	714					
6	Al	5,871,659		02/16/99	Sakano et al.	216	79					
a	AJ	5,908,320		06/01/99	Chu et al.	437	743					
60	AK	5,946,568		08/31/99	Hsiao et al.	438	253					
61	AL	6,074,488		06/13/00	Roderick et al.		118	728				
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				Date	Country		Class	Subclass	Translation			
GC	AM	0 680 084	 A1	28.04.95	EPO (Texas Instrum	ents Inc.)			Yes	No		
G,	AN	WO 98/497	19	05.11.9,8	WIPO (Micron Tech							
	AO			C								
		ОТНЕ	R REF	ERENCES (ir	cluding Author, Title, D	ate, Pertinent Pa	ages, Etc	:.)				
61	AP	Abatch	iev et a	al., Study of	the Boron-Phosphoro	us Doped and U	Undoped	Silicate	Glass Etc	hing in		
		CHF3/Ar Plasma, 96 ELECTROCHEM. Soc. PROCEEDINGS, No. 12, pp. 522-530 (1996).										
	AQ	· · · · · · · · · · · · · · · · · · ·										
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Ei	AA	6,0	74,958	06/13/00	Tokunaga et al.		438	724		RES
EL	AB	6,1	17,788	09/12/00	Ко		438	706 60 72 723 74 70 644 70 396		,
EL	AC	6,1	17,791	09/12/00	Ko et al.		438	723	37	1
6i	AD	6,1	21,671	09/19/00	Ko et al.		257	644	18	, (L)
EL	AE	6,1	53,490	11/28/00	Xing et al.		438	396	1. 19	
EL	AF	6,1	59,862	12/12/00	Yamada et al.		438	712	(X)	
EL	AG	6,10	65,880	12/26/00	Yaung et al.		438	592		
Ci	АН	6,1	71,970 B1	01/09/01	Xing et al.	·	438	706		•
EL	AI	6,1	74,451 B1	01/16/01	Hung et al.		216	67		·
Ü	3	6,1	83,655 B1	02/06/01	Wang et al.		438	723		
CL	AK	6,2	54,966 B1	07/03/01	Kondo		428	156	:	
a	AL	6,3	37,285 B1	01/08/02	Ко		438	714		
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a	**	6,4	32,833 B1	08/13/02	2	C o			438	71	4		
EL	АВ	6,4	58,685 B1	10/01/02	2	Co et al.			438	62	1	•	
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U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

ATTY. DOCKET NO. MI22-2042

SERIAL NO. 09/579,402

APPLICANT: Kei-Yu Ko

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EL	AL	61-133555 0 465 044 A2	12.03.84 19.06.91	Japan (NEC, Ltd.) EPO (AT&T)			X				
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64		contact holes and vias, 7 J. VAC. Sci. Technol. A., No. 3, pp. 670-675 (May/June 1989).									
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